



RenoNix 200mm ESC Profile

2020.01.07



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1-1. Company Profile

Established 04th November 2010

Business Semiconductor tools marketing, Refurbishment, Installation, Relocation, Conversion & Modification, Parts outsourcing, Technical Service, On call service & Technical Development & manufacturing

Capital 330K USD

Employee 16 Persons

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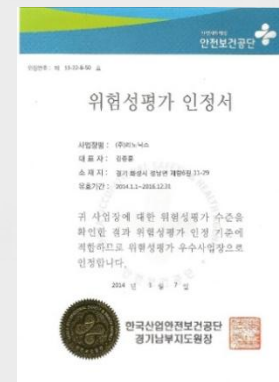
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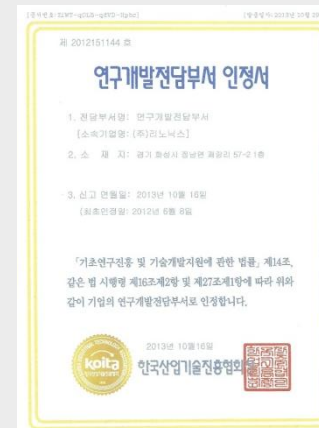
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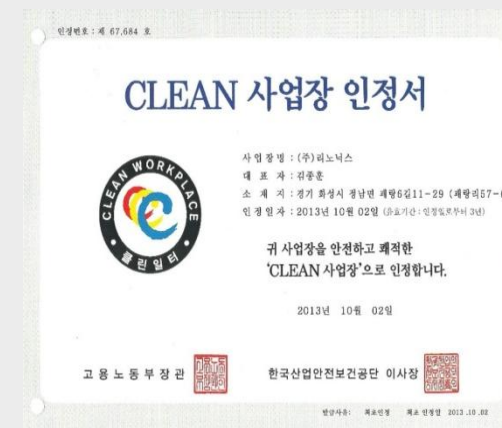
✓Enterprise Risk Management
13-22-B-50



✓Research Institute
2012151144



✓Clean Industry
67,684



1-2. Project Record (The Most Recent 3 Years)

Customer	Project Name	Brief Description	Q'TY	Year
Korea	DxZ PE SiH4 System Controller	Relocation	1	2019
Korea	CxZ Giga Fill Process Conversion From PSG to BPSG	Conversion	1	2019
Korea	Endura PCII Chamber Addition	Addition	1	2019
Korea	WxZ 4 Chamber Dual Divert	Conversion	1	2019
Korea	HDP SPEED USG 3 Chamber	Relocation	1	2019
Czech	Endura Back Metal 4 Chamber	Refurbish & Set-up	1	2019
Korea	CxZ Chamber From Bottom RPS to Top RPS	Conversion	1	2019
Singapore	Endura System From 6" to 8"	Conversion	1	2019
Korea	CxZ Chamber From Bottom RPS to Top RPS	Conversion	1	2019
Korea	Endura Chamber From HTHU Heater to STF 4F Heater	Conversion	1	2018
Korea	DxZ PE TEOS 4 Chamber	Refurbish & Set-up	1	2018
USA	2 WxZ Chamber, 2 WxP Chamber	Refurbish & Set-up	1	2018
Korea	WxZ 4 Chamber Dual Divert	Conversion	1	2018
Korea	DLH PE SiH4 3 Chamber	Relocation	1	2018
Korea	AMAT Centura TPCC DPN	Refurbishment/Start up	1	2017
Singapore	AMAT Endura5500 Ai Cu	Refurbishment/Start up	1	2017
USA	AMAT Centura	Refurbishment	1	2017
Korea	AMAT Producer-S 200mm	Refurbishment	1	2017
Korea	AMAT Endura5500 MOCVD	Retrofit & Start up	1	2017
Korea	AMAT Centura WCVD	Refurbishment/Start up	1	2017

1-3. Project Record (The Most Recent 9 Years)

Summary list for project

Project Name	Endura	Centura	Producer	LAM / Novellus	TEL SCCM	DNS	Other	TOTAL
Refurbishment/ Start up	18	8	2	2	1	1	5	37
Retrofit / Start up	22	10	-	-	-	-	3	35
Relocation/ Start up	1	12	-	1	-	-	4	18
Refurbishment	6	2	2	-	1(Upgrade)	-	3	14
TOTAL (104)	47	32	4	3	2	1	15	104

Summary list for country

Country	Q'TY	Rate
Korea	54	52%
China	18	17%
Singapore	18	17%
Taiwan	8	8%
Other	6	6%
TOTAL	104	100%

1-4. Business Detail

Customer Satisfaction

Equipment Refurbish

- ✓ AMAT PVD / CVD / ETCH, LAM / Novellus ETCH / CVD, PSK TERA / SUPRA, TEL ETCH / TRACK, DNS Scrubber, etc.
- System Refurbishment, Modification, Relocation, Upgrade & Conversion Start-up.

2nd / OPM NEW Overhaul Items

- ✓ Shower Head 2nd NEW (200mm / 300mm)
- ✓ Magnet 2nd NEW (150mm / 200mm)
- ✓ Ceramic Heater 2nd NEW
- ✓ Heater Block 2nd NEW (150mm / 200mm)
- ✓ WJ 999 / 1000 / 1500 EQUIP Parts 2nd NEW

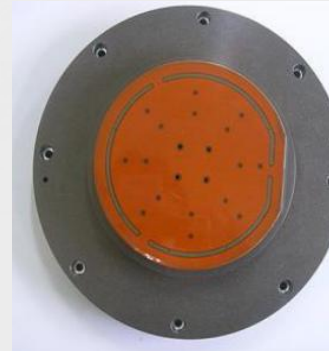
Spare Parts

- ✓ OEM / OPM / 2nd New Parts
- ✓ OPM : LAM Electrode / Stud Socket / ESC / ALN Heater / Gasket etc.
- ✓ 2nd New : Ceramic Pin.
- ✓ Provide process kits for PVD, CVD, ETCH process chamber.
- ✓ AMAT / LAM / NOVELLUS DNS / TEL etc. system part.

2-1. ESC 2nd NEW

➤ ESC 2nd NEW Items

Polymide ESC's are widely used on semiconductor manufacturing equipment such as AMAT, LAM, TEL.



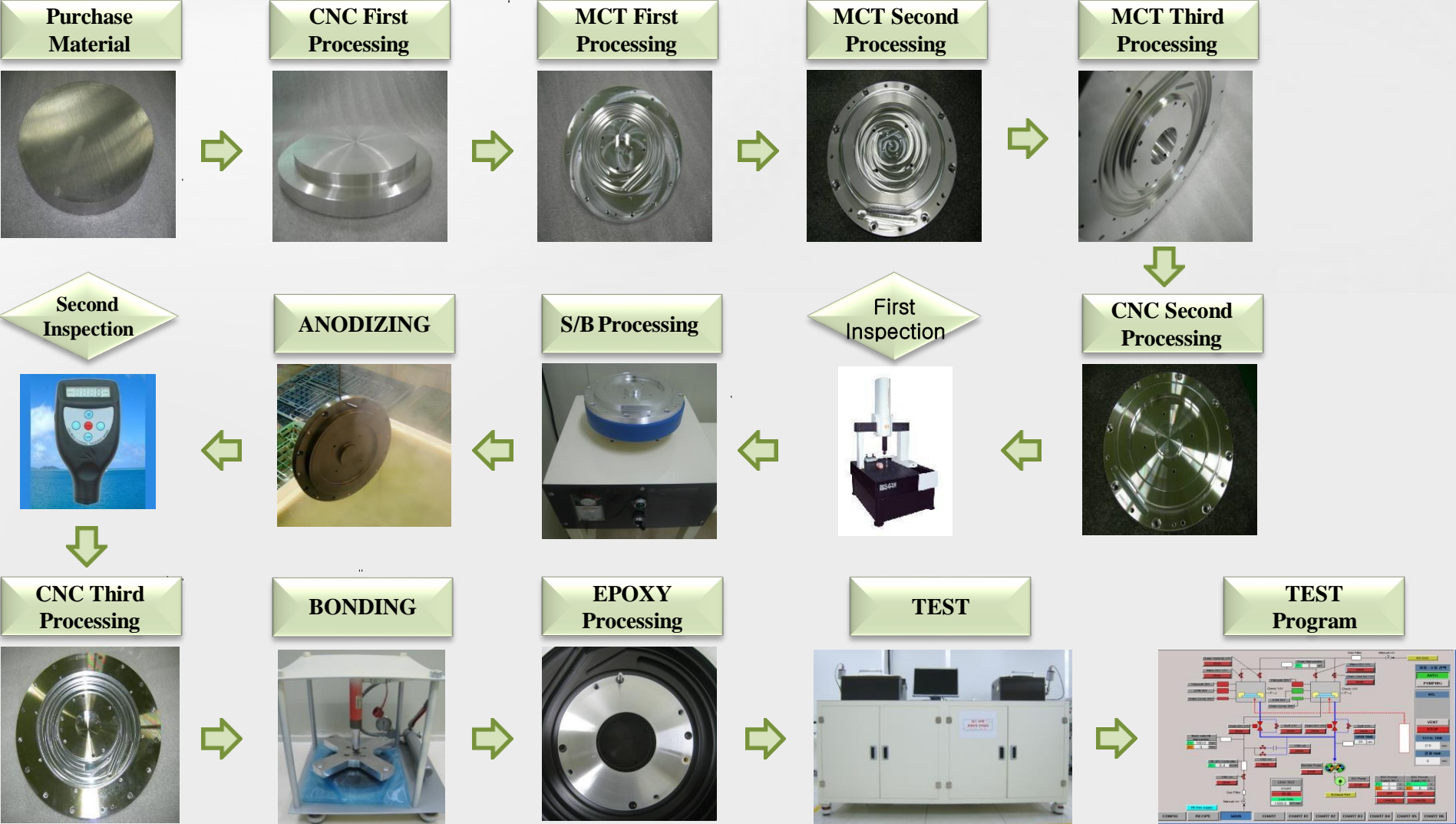
Recently, domestic product of ESC used in ETCH Process has shown fail trend during Production.

The following problem has shown during production.

- ◆ *System up time decrease*
- ◆ *Cost Increase*
- ◆ *Lower Quality*
- ◆ *PM time Increase*

Therefore, RenoNix here to introduce an product which has qualified by other foundries.

2-2. ESC Production Flow Chart



2-3. ESC Final Inspection Report & Packaging Flow Chart

Final Inspection Report

Normal Information

Report No.	RNESC20181210-1	Date	2018.12.10
Parts No.	718-094523-281	Description	LAM ESC 8"

Material Information

ESC Type	Bipolar Type	Equipment	LAM TCP
Material	AL6061	Dielectric	Anodizing

Test Data

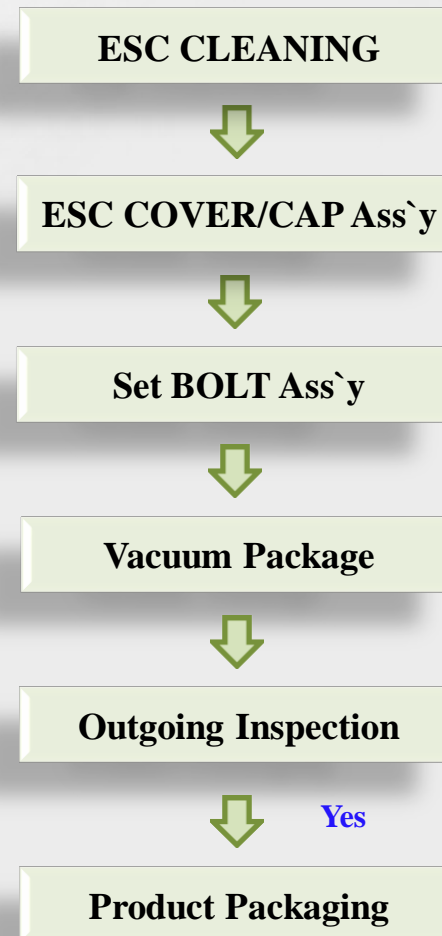
Description	Spec	Result	Judge	
Anodizing Thickness	50 ± 5µm	52.5	PASS	
Anodizing Roughness	≤ 0.8 Ra	0.72	PASS	
Donut Recess	≤ 8µm	7	PASS	
Capacitance	3.5-5.5nF	5.18	PASS	
Withstand Voltage	1.0KV, dwell 10sec	OK	PASS	
Chucking Flow	20 torr ↑, dwell 120sec	OK	PASS	
Maximun Flow	≥25 torr	31.2	PASS	
He Leakage (DC 700V)	0.3-4.0 sccm at 10 torr	2.21	PASS	
	0.6-6.0 sccm at 15 torr	3.80	PASS	
	1-8.0 sccm at 20 torr	4.53	PASS	
Wafer Sticky	≤20 secons release time	6.21	PASS	

Torr	5	10	15	20	25	30	He Flow
sccm	1.23	2.21	3.80	4.53	5.21	5.94	5 Sccm

Visual


Description	Spec	Result	Judge	Remark
Color	Black Brown	OK	PASS	
Scratch	Visual Inspection	OK	PASS	
Crack	Visual Inspection	OK	PASS	
He Hole	Visual Inspection	OK	PASS	


ESC Packaging Flow Chart



2-4. ESC 2nd NEW Items (I)

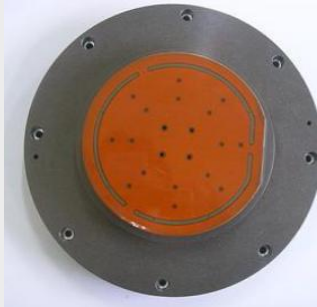
➤ TEL ESC (200mm)


TEL P/N.	16-271392-00	Capacitance	8.0 ~ 12nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TE-8500 8" UNITY-II-85DP	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness	45 ± 5μm	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	
Roughness	≤ 0.8Ra			

TEL P/N.	1810-120900-13	Capacitance	8.0 ~ 12nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TE-8500 8" Jeida UNITY-II-85DP	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness	45 ± 5μm	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	
Roughness	≤ 0.8Ra			

2-4. ESC 2nd NEW Items (II)

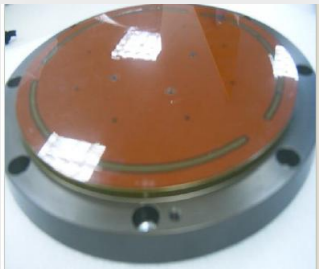
➤ TEL ESC (150mm / 200mm)


TEL P/N.	1810-121296-12 1885-022353-17	Capacitance	8.0 ~ 12nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TEL TE-8500 6" UNITY-II-DP 6"	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness	45 ± 5μm	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	
Roughness	≤ 0.8Ra			

TEL P/N.	1810-121603-11	Capacitance	8.0 ~ 12nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TEL UNITY-II-85DI 8" (IEM-8J-UP)	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness	45 ± 5μm	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	
Roughness	≤ 0.8Ra			

2-4. ESC 2nd NEW Items (III)


➤ TEL ESC (200mm)


TEL P/N.	1810-121613-11	Capacitance	8.0 ~ 12nF	Photo 
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TEL UNITY-II-85DI 8" (IEM-NOTCH)	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness Roughness	45 ± 5μm ≤ 0.8Ra	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	

TEL P/N.	1810-121188-11 1810-121189-12	Capacitance	8.0 ~ 12nF	Photo 
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TEL UNITY-II-85DI 8" (IEM-NOTCH)	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness Roughness	45 ± 5μm ≤ 0.8Ra	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	

2-4. ESC 2nd NEW Items (IV)


➤ TEL & AMAT ESC (200mm)


TEL P/N.	1D10-100956-12	Capacitance	8.0 ~ 12nF	Photo 
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	TEL UNITY-II-85DD 8"	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness Roughness	45 ± 5μm ≤ 0.8Ra	Chucking Force	50 ± 20Torr, dwell 120sec, (Center & Edge)	

AMAT P/N.	0090-35112 0020-38733 / 39834	Capacitance	6.0 ~ 9.0nF	Photo 
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	AMAT CENTURA MxP-5200 Metal 8"	He Pressure	< 6 min, 20Torr ↑ (Center & Edge)	
Anodizing Thickness Roughness	30 ± 10μm ≤ 0.8Ra	Chucking Force	30 ± 10Torr, dwell 120sec	

2-4. ESC 2nd NEW Items (V)


➤ AMAT ESC (150mm / 200mm)


AMAT P/N.	0040-09956 / 99964 0010-10527	Capacitance	2.0 ~ 5.0nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	AMAT CENTURA MxP-5200 Poly 6" / 8"	Anodizing Thickness Roughness	55 ± 5μm	
			≤ 0.8Ra	

AMAT P/N.	0020-34862 / 99952 0010-10982	Capacitance	8.0 ~ 12nF	Photo
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 120sec	
Equipment	AMAT P5000 Oxide 6"	Anodizing Thickness Roughness	45 ± 5μm	
			≤ 0.8Ra	

2-4. ESC 2nd NEW Items (VI)


➤ AMAT & LAM ESC (150mm / 200mm)


TEL P/N.	0090-35133 (Soft Anodizing)	Capacitance	6.0 ~ 9.0nF	Photo 
Type	Unipolar Polyimide	Withstand Voltage	1.8kV, dwell 10sec	
Equipment	AMAT CENTURA DPS 6" / 8"	Chucking Force	30 ± 10Torr, dwell 120sec	
Anodizing Thickness	30 ± 10 μ m	Anodizing Roughness	≤ 0.8Ra	

LAM P/N.	718-094523-282	Capacitance	2.0 ~ 3.5nF	Photo 
Type	Bipolar Polyimide	Withstand Voltage	1.0kV, dwell 10sec	
Equipment	LAM Anodizing 8" FLTD	Chucking Force	20Torr ↑, dwell 120sec	
Anodizing Thickness	50 ± 5 μ m	Anodizing Roughness	≤ 0.8Ra	

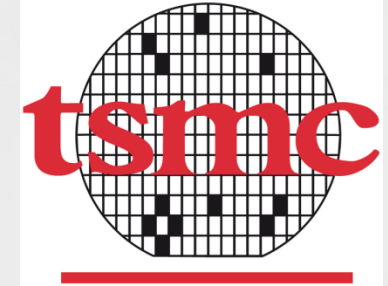
2-4. ESC 2nd NEW Items (VII)

➤ LAM ESC (150mm / 200mm)

LAM P/N.	718-094523-281	Capacitance	2.0 ~ 3.5nF	Photo 
Type	Bipolar Polyimide	Withstand Voltage	1.0kV, dwell 10sec	
Equipment	LAM Anodizing 8" Notched	Chucking Force	20 Torr↑, dwell 120sec	
Anodizing Thickness	50 ± 5μm	He Leakage (DC700V)	0.3~4.0 SCCM at 10Torr	

LAM P/N.	718-094523-261 718-092326-061	Capacitance	2.0 ~ 3.5nF	Photo 
Type	Bipolar Polyimide	Withstand Voltage	1.0kV, dwell 10sec	
Equipment	LAM Anodizing 6" MJR FLT	Chucking Force	20Torr↑, dwell 120sec	
Anodizing Thickness	50 ± 5μm	Anodizing Roughness	≤ 0.8Ra	

RenoNix Major Customer



Contact Point

**We're Capable of Most of service for PVD,CVD, ETCH areas.
If you have any inquiry or interest , please feel free to contact us.**



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